## **REMARKS**

At the outset, the Examiner is thanked for the thorough review and consideration of the subject application. The Office Action of February 11, 2005 has been received and contents carefully reviewed. Applicants gratefully acknowledge the Examiner's indication of allowable subject matter in claim 7.

Claims 1-2 and 4-20 are currently pending in the present application. Reexamination and reconsideration of the application are respectfully requested.

In the Office Action, the Examiner rejected claims 1, 2, 4-6, and 8-20 under 35 U.S.C. § 103(a) as being anticipated by <u>Kim et al.</u> (U.S. Patent No. 6,038,008) in view of <u>Kim</u> (U.S. Patent No. 6,060,130); and rejected claims 1, 2, 4-6, and 8-20 under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1-10 and 15-17 of U.S. Patent No. 6,038,008 in view of <u>Kim</u>.

The rejection of claims 1, 2, 4-6, and 8-20 under 35 U.S.C. § 103(a) as being anticipated by <u>Kim et al.</u> in view of <u>Kim</u> is respectfully traversed and reconsideration is requested.

Claim 1 is allowable over the cited references in that claim 1 recites a combination of elements including, for example, "irradiating the organic passivation layer with ultraviolet rays having a wavelength in a range between about 100 nm and about 200 nm to form a hydrophilic buffer layer having a thickness of 10Å to 50Å..." None of the cited references including Kim et al. and Kim, singly or in combination, teaches or suggests at least this feature of the claimed invention. Accordingly, Applicants respectfully submit that claim 1, and claims 2, 4-6 and 8, which depend therefrom, are allowable over the cited references.

Claim 9 is allowable over the cited references in that claim 9 recites a combination of elements including, for example, "a hydrophilic buffer layer having a thickness of 10Å to 50Å over said passivation layer, the buffer layer formed by irradiating the organic passivation layer with ultraviolet rays having a wavelength in a range between about 100 nm and about 200 nm..." None of the cited references including <u>Kim et al.</u> and <u>Kim</u>, singly or in combination, teaches or suggests at least this feature of the claimed invention. Accordingly, Applicants respectfully submit that claim 9, and claims 10-20 which depend therefrom, are allowable over the cited references.

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The specification of the present application at page 9, lines 11-14 discloses, "since UV rays having a wavelength of about 100 to 200 nm have high energy, oxygen in the air is excited and some becomes ozonized... a UV ray passing through the ozonized oxygen forms a molecular combination with the surface of the organic insulating film such that a buffer layer 49 having a hydrophilic property is formed." Accordingly, Applicants respectfully submit that the claimed invention is distinguishable over the cited references including Kim et al. and Kim.

For at least similar reasons discussed above, the rejection of claims 1, 2, 4-6, and 8-20 under the judicially created doctrine of obviousness-type double patenting is traversed.

Applicants believe the application is in condition for allowance and early, favorable action is respectfully solicited. If the Examiner deems that a telephone conference would further the prosecution of this application, the Examiner is invited to call the undersigned attorney at the telephone number (202) 496-7500. All correspondence should continue to be sent to the belowlisted address.

If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time, or any other fees required to complete the filing of this response, may be charged to Deposit Account No. 50-0911. Please credit any overpayment to deposit Account No. 50-0911.

Dated: July 1, 2005

Respectfully submitted,

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